

8. LECTURE: THE INVERTER. MOS DIGITAL CIRCUITS I.

1. The inverter: properties and functions

- 2. The MOS system, basic properties
- 3. MOSFET and basic MOS circuits
- 4. The CMOS concept, CMOS logic circuits





































IDEAL INVERTER

For a gate to be robust and insensitive to noise disturbances it is important that the '0' and '1' regions be as far apart as possible.

Some of the properties of the ideal digital gate

has the following properties infinite gain in the transition region with the threshold voltage in the middle of the logic swing,

with high and low margins equal to half the swing,

the input and output impedance (resistance) are infinity and zero.

POWER DISSIPATION

Power is the product of current by voltage and is dissipated within a digital IC during switching.

The static dissipation is equal to the product of the dc voltage and the mean current taken from the supply.

$P_{static} = I V = V_{DD}^2/R$

For bipolar devices the power dissipated at the maximum frequency is usually about 20% greater that the static dissipation.

By contrast in a CMOS device the power dissipated is very small - this is one of the main advantages of CMOS over TTL based devices.







LOGIC FAMILIES

Logic family: homogeneous circutis and networks with common unified proerties:

same supply voltage

same logic levels

similar propagation delays

same technology (usually on one chip)







A COMPARISON OF LOGIC FAMILIES

Basic gate NAND/N Fan-out >50	IOR NAND	OR/NOR
Fan-out >50	10	25
		25
Power per gate (mW) 1 @ 1 M	1Hz 1 - 22	4 - 55
Noise immunity Excelle	ent Good	Acceptable
<i>t_{PD}</i> (ns) 1 - 20	0 1.5 – 33	3 1 - 4

INTRODUCTION TO THE MOS TRANSISTOR

The invention of the transistor action (electrical signal amplification) in semiconducting material was a monumental accomplishment that has revolutionized the world. As with many inventions, the structure of the original invention has not only evolved, but also led to new structures. The first demonstration of transistor action (*Bardeen, Brattain*), the original point-contact transistor, was soon followed by the invention of the junction bipolar transistor (*Shockley*). This second structure is viewed as the basis of modern microelectronics, because it laid the foundation for the concept of building an entire electrical circuit on a single piece of semiconducting material (*Kilby, Noyce*).











INTRODUCTION TO THE MOS TRANSISTOR

It is interesting to recognize, however, that the junction bipolar transistor and the technology that was developed to fabricate it led to another type of transistor, the metal-oxidesemiconductor (MOS) transistor. Both the theory of MOS transistor operation and the technology associated with its fabrication were derived from the classic junction bipolar structure and related research. Today, however, the MOS transistor is the structure primarily used in the continuing exponential growth of microelectronics (Moore's law).

36

THE MOSFET

The MOSFET has proven to be the device par excellence for integrated circuit logic because of its relative simplicity (compared to bipolar transistors), small size, and low power demands (in large part because of its infinite input resistance); only in the area of speed does MOSFET logic circuitry fall short of bipolar logic circuitry.

In the followings we will look at several MOSFET logic families. They are all basically common-source circuits and differ only in the nature of their load devices.

37







J. LILIENFELD AND THE FET

Julius Edgar Lilienfeld (1882-1963) was a physicist of Polish origin. He was born in Lemberg, Galicia, in the Austrian-Hungarian Monarchy (now called Lviv in Ukraine), moved to the United States in the early 1920s.

Lilienfeld is credited with the first patents on the field effect transistor (1920s) and electrolytic capacitor (1931).

He filed several patents describing the construction and operation of transistors as well as many features of modern transistors. (US patent #1,745,175 for an FET-like transistor was granted January 28, 1930.) When Brattain, Bardeen, the future Nobelist, and Robert Gidney tried to get patents on their earliest devices, most of their claims were rejected due to the Lilienfeld patents.















THE IC TODAY: THE 45 nm TECHNOLOGY

Atom probe tomography

The solute distributions across a 32 nm technology nFET transistor extracted by a focused ion beam-based technique from a commercial Intel® i5-650 microprocessor is shown in an atom map in fig.

The gate oxide was found to be 80 at. % Hf+O, 20 at. % Si, the source and drain regions either side of the channel region contained a maximum of 25 at. % Ge. The distributions of the B and As atoms are clearly shown in relationship to the source and drain regions.







































- MOSFET occupies the smallest area on the Si wafer
- MOSFET can be fabricated with less number of steps
- MOSFET is controlled with practically zero power
- In stationary state it does not draw current from the supply
- Supply voltage can vary in a wide range
- No resistors are necessary











REVISION QUESTIONS

1. Define the concept of logic family.

2. Explain the governing parameters of the logic families.

3. Describe the difference between the bipolar integrated circuits and MOS integrated circuits.

4. What is noise immunity? What is propagation delay?

5. Describe the characteristics of MOS logic.

6. Describe enhancement type MOS and depletion type MOS with constructional details.

END OF LECTURE